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INTERMEDIATE LAYER MATERIAL COMPOSITION FOR THREE-LAYER RESIST PROCESS AND PATTERN FORMING METHOD USING THE SAME

Abstract:

PROBLEM TO BE SOLVED: To provide an intermediate layer material composition for a three- layer resist process soluble in an organic solvent, excellent in storage stability and free of a problem in trailing shape and line edge roughness in patterning of an upper layer resist and to provide a pattern forming method using the composition.

SOLUTION: The intermediate layer material composition comprises (A) a polymer having an octakis (sesquioxane) skeleton obtained by bringing a polysiloxane compound having a cyclic structure and a bis (substituted ethynyl) compound into hydroxylation polymerization reaction in the presence of a platinum-containing catalyst.

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